



Dr. Victor M. Blanco Carballo

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Victor M. Blanco Carballo received his Ph. D degree in Microelectronics from University of Twente in 2009 followed by a post-doctoral position in high energy physics at NIKHEF (Amsterdam) He joined ASML in 2011 where he worked as architect improving defectivity and throughput of immersion and EUV systems. In 2017 he joined imec working as a researcher in EUV lithography and metrology under the ASML/imec Advanced Patterning Center.

Currently he is a principal member of the technical staff and team lead for the patterning pathfinding team addressing industry relevant technology gaps for the N2/N2+ nodes.